

Development of fast and high precision CMOS pixel sensors for an ILC vertex detector

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Outline

- ❖ *MIMOSA26 design and test results*
 - *Comparison normal and high resistivity EPI*
- ❖ *Sensor design plan for the coming 2-3 years*
 - *Innermost layer sensors design*
 - *Outer layer sensors design*
- ❖ *Conclusion*

Development of CMOS Pixel Sensors for Charged Particle Tracking

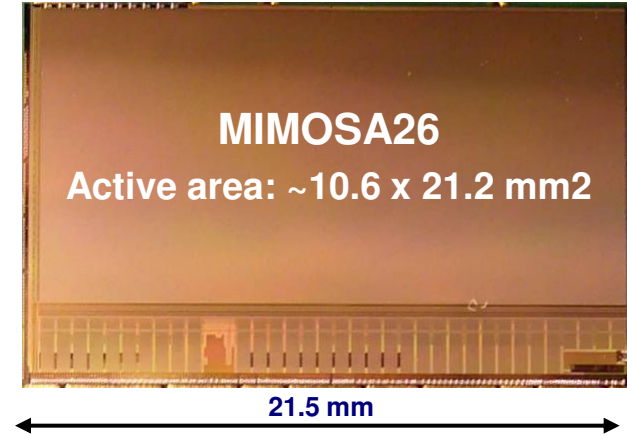
- 2009, an important year for CMOS pixel sensors R&D: MIMOSA26 has been designed, fabricated and tested within the EUDET program

- MIMOSA26 is a reticule size MAPS with binary output, 10 k images / s

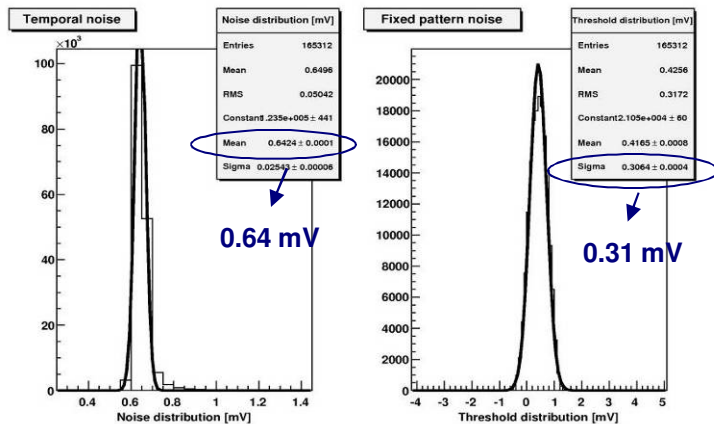
↪ Pixel array: 1152 x 576, 18.4 μm pitch

↪ Architecture:

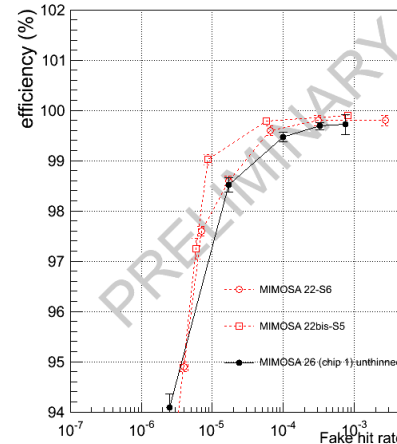
- Pixel (Amp+CDS) array organised in // columns r.o. in the rolling shutter mode
- 1152 ADC, a 1-bit ADC (discriminator) / column
- Integrated zero suppression logic
- Remote and programmable



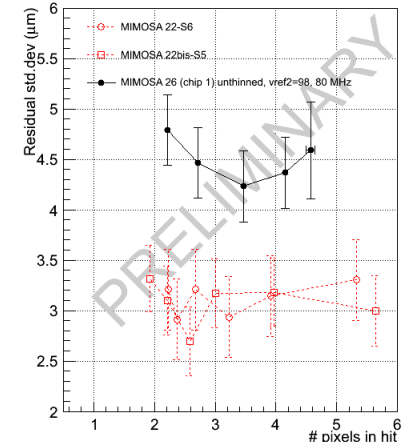
- Lab. and beam tests: 62 chips tested, yield ~75%



ENC ~ 13-14 e⁻



Efficiency 99.5% for fake rate 10⁻⁴



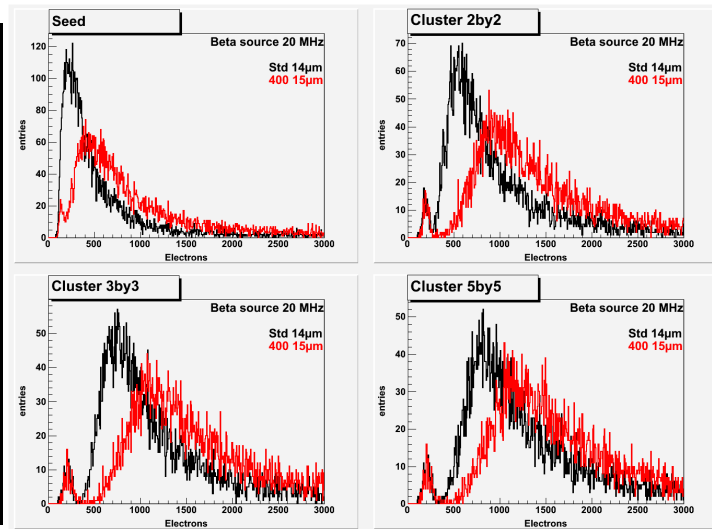
Single point resolution ~4 μm

MIMOSA26 Test

- Standard EPI layer (fab. end 2008) v.s. high resistivity EPI layer (fab. end 2009)

↪ Charge collection & S/N (Analogue output, Freq. 20 MHz)

EPI layer	Standard (~10 Ω.cm) 14 μm			High resistivity (~400 Ω.cm)			
	Seed	2x2	3x3	EPI	seed	2x2	3x3
Charge Collection (⁵⁵ Fe source)	~21%	~54%	~71%	10 μm	~36%	~85%	~95%
				15 μm	~31%	~78%	~91%
				20 μm	~22%	~57%	~76%
S/N at seed pixel (¹⁰⁶ Ru source)	~20 (230 e ⁻ /11.6 e ⁻)			10 μm	~35		
				15 μm	~41		
				20 μm	~36		



↪ Radiation test under way for applications more demanding than ILC

- Ionising TID: 150 K, 300 K, 1M Rad
- Non Ionising NIEL: 3×10^{12} , 6×10^{12} , 1×10^{13} , 3×10^{13} N_{eq}/cm^2

- MIMOSA26 can be operated at a high readout speed

↪ Clock frequency: from 80 MHz_{typ.} (~110 μs) up to 110 MHz (~80 μs)

➔ MIMOSA26: design base line for STAR Vx upgrade, CBM MVD
Its performances are close to the ILD vertex detector specifications

ILC VTX : R&D of CMOS Sensors

■ Innermost layer sensors:

↙ $t_{int.} \sim 25 \mu s$

$\sigma_{sp} < 3 \mu m$

R&D effort on high readout speed design

- Double-sided readout (for both design options)
- Elongated pixels (for 3 double layers option: time stamp tier)

■ Outer layer sensors:

↙ $t_{int.} < \sim 100 \mu s$

$\sigma_{sp} \sim 3-4 \mu m$

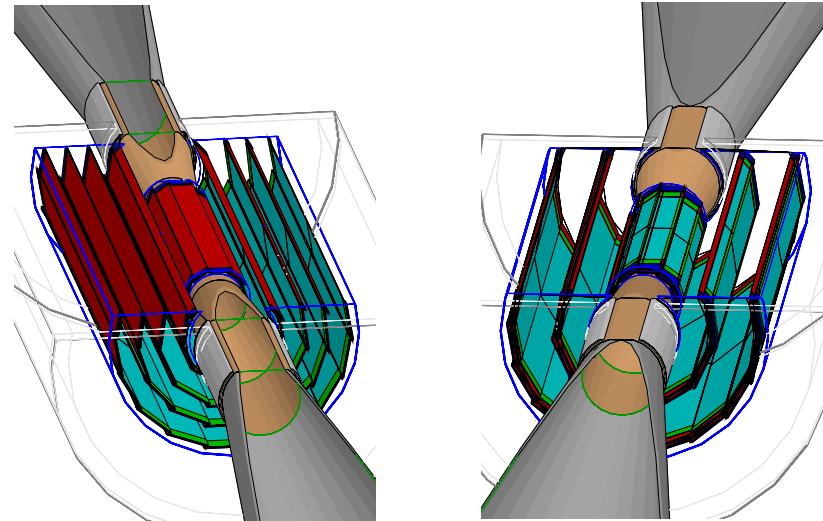
R&D effort on low power consumption design

- Single-sided readout (for both design options)
- 4-bit column-level ADCs

■ Power consumption:

↙ $P_{diss} < 0.1-1 W/cm^2$ ($\times \sim 1/50$ duty cycle)

ILD design: 2 options



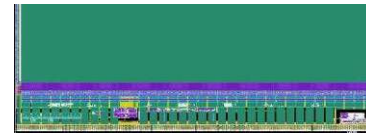
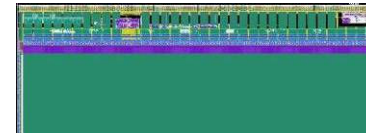
5 single layers

3 double layers

Innermost Layer CMOS Sensor's Development

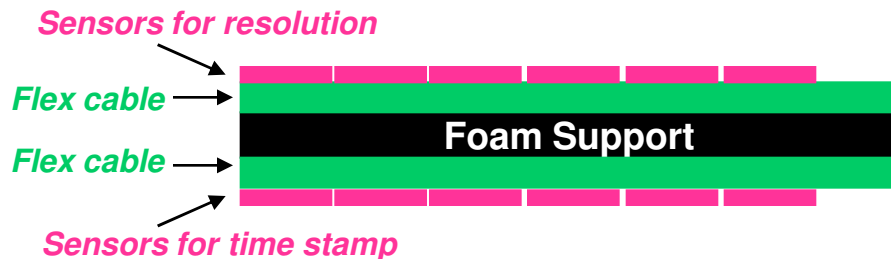
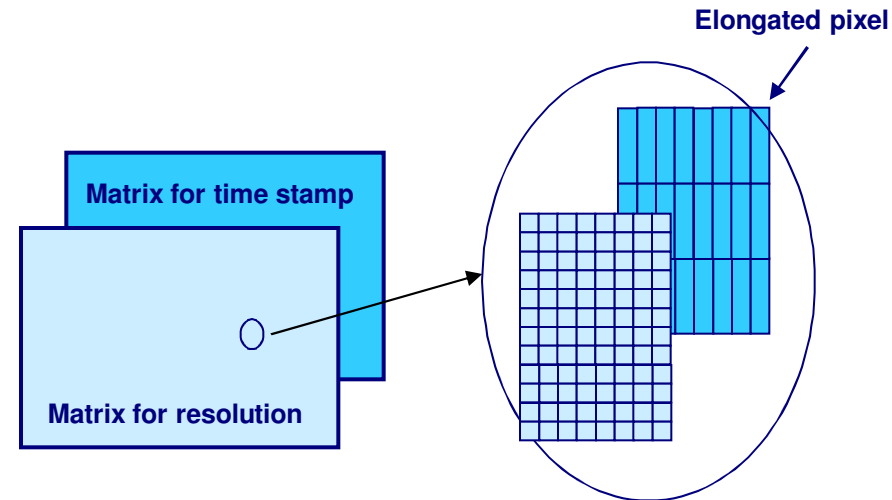
■ 1st R&D line: double-sided readout

- ↳ Based on architecture of MIMOSA26
 - Rolling shutter readout mode + A/D conversion
 - ➔ binary output + zero suppression
- ↳ Pixel array: $\sim 14 \mu\text{m}$ pitch
- ↳ Active area: $\sim 9 \times (\sim 20) \text{ mm}^2$
- ↳ $t_{\text{int.}} < \sim 40\text{-}60 \mu\text{s}$
- ↳ $P_{\text{diss}} < \sim 1 \text{ W/cm}^2$ ($\times \sim 1/50$ duty cycle)



■ 2nd R&D line: elongated pixels

- ↳ Time stamp tier for 3 double layers option
 - Ex: $14 \times (4 \times 14 \mu\text{m})$
- ↳ $t_{\text{int.}} < \sim 10\text{-}15 \mu\text{s}$
- ↳ High resistivity EPI process useful
 - High charge collection efficiency



"Plume" Project ➔ Integration topic
Collaboration: Strasbourg, DESY,
 Oxford, Bristol, ...

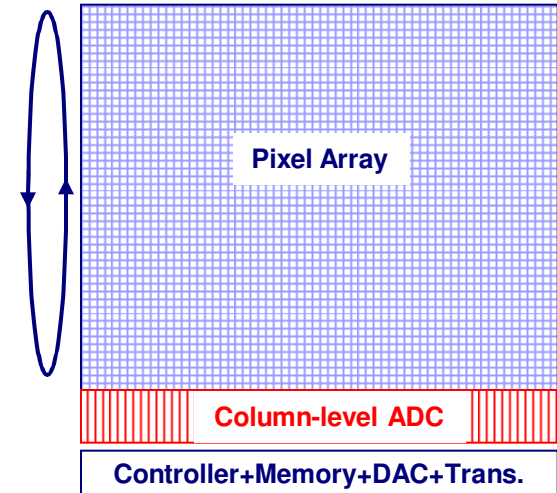
See Nathalie Chon-Sen's talk:

ILC Outer layer CMOS Sensor's Development

- Large pitch pixels associated with column-level ADC
→ power consumption reduction

- Single-sided readout

- ↪ Pixel array: 576 x 576, pitch 35 μm
- ↪ 4-bits ADC / column
- ↪ $t_{\text{int.}} \sim 60 - 100 \mu\text{s}$
- ↪ $P_{\text{diss}} < \sim 0.2 \text{ W/cm}^2$ ($x \sim 1/50$ duty cycle)



- Different column-level ADC architectures have been investigated in IN2P3-CEA collaboration
- Taking integration experience of MIMOSA26, ADC's architecture will be extended to several hundreds ADCs converting all signals of a row simultaneously
 - ↪ Noise from substrate coupling
 - ↪ Coupling between ADC
 - ↪ Long common reference line ($\sim 2 \text{ cm}$) for whole chip
 - ↪ Offset compensation
 - ↪ Clock and control signals management
- Submission of a small sensor but a sizable prototype: pixel array + column-level ADC

Exploration of new process

→ *Using a smaller feature size CMOS technology: 0.18 μm*

↳ *High speed operation inside chip*

↳ *Surface reduction in digital design*

↳ *Reduce power consumption ...*

↳ *Offer more metal layers for interconnection → decrease dead zone*

■ *MIMOSA27 in a 0.18 μm process (up to 6 metal layers) will be submitted on April 9th, 2010*

↳ *10 mm², 20 μm pitch, 4 sub-matrices of 64 x 64*

■ *Up to 16 options:*

Diode size and type of configuration

3 T and self-bias

In pixel amplification

■ *Study:*

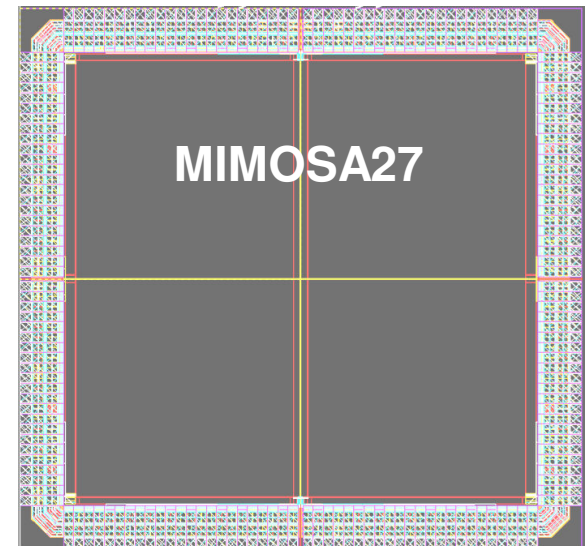
Charge collection efficiency

Technology features

Signal to noise ratio

Radiation hardness

...



Using 3DIT to improve MAPS performances (1)

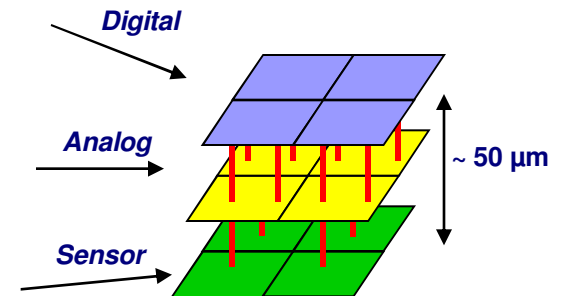
■ 3DIT are expected to be particularly beneficial for MAPS :

↪ **Combine different fabrication processes** → **Split signal collection and processing functionalities** → **use best suited technology for each Tier :**

- Tier-1: charge collection system → Epitaxy (depleted or not) → ultra thin layer → X_0 ↓
 - Tier-2: analogue & mixed signal processing → analogue, low I_{leak} , process (No. of metal layers)
 - Tier-3: digital signal processing & data transmission
 - (Tier-4: data transmission, electro-optical conversion ?)
- > digital process (number of metal layers)
feature size → fast laser driver, etc.

↪ **Resorb most limitations specific to 2D MAPS**

- Dead surface ↓
- Power consumption ↓
- Readout speed ↑
- ...



■ 2009: run in Chartered - Tezzaron technology

↪ 3D consortium: coordinated by FermiLab

↪ 130 nm, 2-Tier run with "high"-res substrate (allows m.i.p. detection)

- Tier A to tier B bond → Cu-Cu bond

Using 3DIT to improve MAPS performances (2)

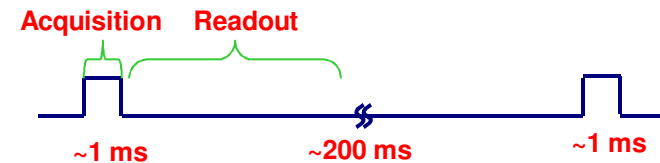
■ Delayed R.O. Architecture for the ILC Vertex Detector (designed & submitted)

↪ Try 3D architecture based on small pixel pitch, motivated by :

- Single point resolution $< 3 \mu\text{m}$ with binary output
- Probability of > 1 hit per train per pixel $\ll 10 \%$

→ $12 \mu\text{m}$ pitch :

- $\sigma_{sp} \sim 2.5 \mu\text{m}$
- Probability of > 1 hit/train/pixel $< 5 \%$

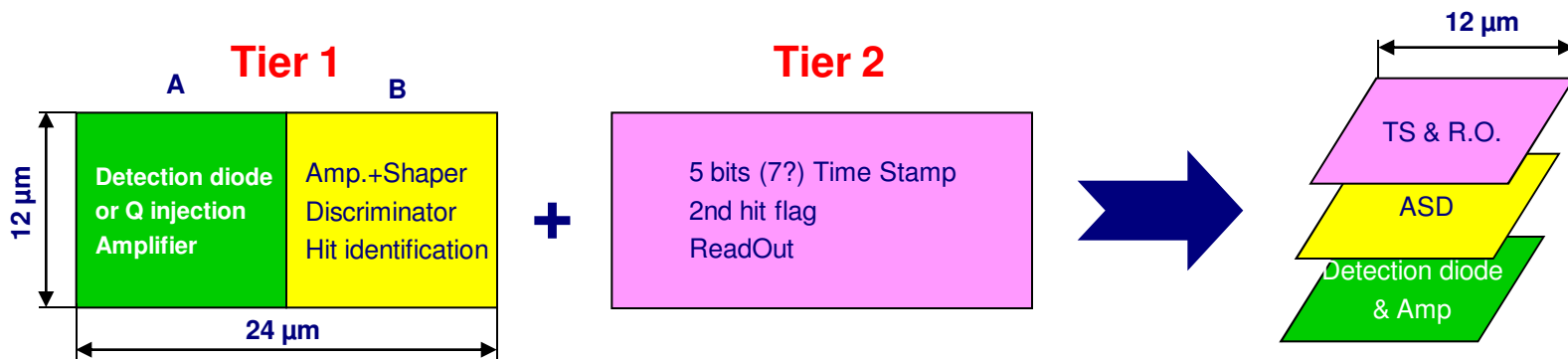


↪ 3D 2-tier process

- Tier-1: A: sensing diode & amplifier, B: shaper & discriminator
- Tier-2: time stamp (5 bits) + overflow bit & delayed readout

→ Architecture prepares for 3-Tier perspectives : $12 \mu\text{m}$

- Tier-1: CMOS process adapted to charge collection
- Tier-2: CMOS process adapted to analogue & mixed signal processing
- Tier-3: digital process ($\ll 100 \text{ nm}$?)

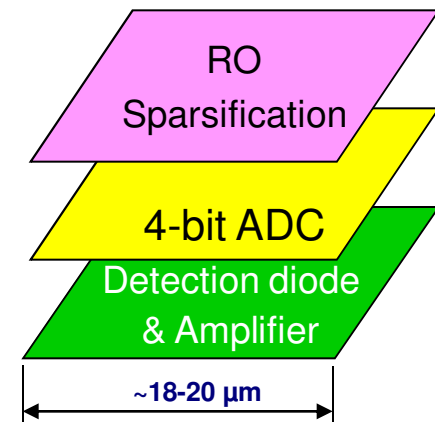
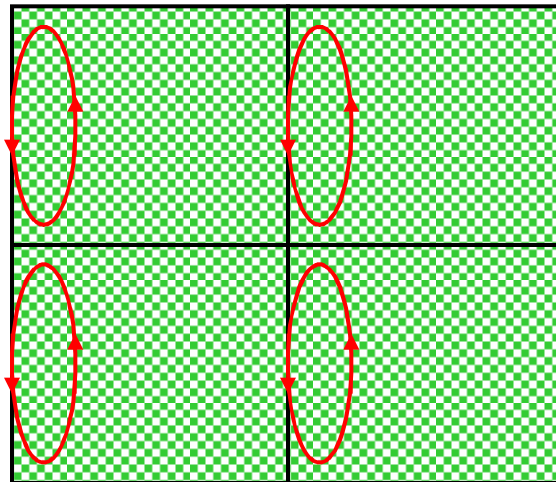


Using 3DIT to improve MAPS performances (3)

■ MAPS with fast pipeline digital readout aiming to minimise power consumption (R&D in progress)

- ↪ Subdivide sensitive area in "small" matrices running individually in rolling shutter mode
- ↪ Adapt the number of rows to required frame readout time
 - ➔ few μs r.o. time may be reached
- ↪ Design in $20 \mu\text{m}^2$:
 - Tier 1: Sensor & preamplifier ($G \sim 500 \mu\text{V}/e^-$)
 - Tier 2: 4-bit pixel-level ADC with offset cancellation circuitry ($\text{LSB} \sim N$)
 - Tier 3: Fast pipeline readout with data sparsification

➔ $\sigma_{sp} \sim 2 \mu\text{m}$
 $T_{int.} < 10 \mu\text{s}$



Conclusion

- **MIMOSA26's performances are close to ILD vertex detector specifications**
 - ➔ **Architecture will evolve to meet VTX performances**
 - ↪ Innermost layer: double sided readout ➔ readout speed trade-off
 - ↪ Outer layer: matrix + column-level ADC ➔ power consumption trade-off
- **Fabrication processes with high resistivity EPI layer will improve read-out speed and radiation tolerance**
 - ↪ Time stamp layer
- **Integration of column-level ADCs with pixel array in progress**
- ➔ **Prototyping of inner and outer layer sensors expected to be nearly finalised by 2012 for ILD-DBD**
- **Translation to 3DIT will resorb most limitations specific to 2D MAPS**
 - ↪ Still many difficulties to overcome
 - ↪ Offer an improved read-out speed : $O(\mu\text{s})$ + Lower power consumption